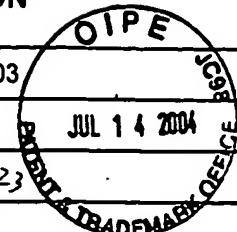


## INFORMATION DISCLOSURE CITATION



Atty. Docket No.	2887.0261	Appln. No.	10/730,903
Applicant	Saito		
Filing Date	December 10, 2003	Group:	28112823

## U.S. PATENT DOCUMENTS

Examiner Initial*	Document Number	Issue Date	Name	Class	Sub Class	Filing Date If Appropriate
W/B	6,054,355	4/25/00	Inumiya et al.	438	296	X

## FOREIGN PATENT DOCUMENTS

	Document Number	Publication Date	Country	Class	Sub Class	Translation Yes or No
W/B	2000-294557	10/20/00	Japan	X	X	Abstract

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

W/B	Saito et al., "Plasma-Damage-Free Gate Process Using Chemical Mechanical Polishing for 0.1 μm MOSFETs," Jpn. J. Appl. Phys. (April 1999), 38:2227-31

Examiner	William M. Bremner	Date Considered
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INFORMATION DISCLOSURE CITATION

Application No. 02887.0261	Application No. 10/730,903
Applicant Tomohiro SAITO	
Filing Date December 10, 2003	Group: 2823

U.S. PATENT DOCUMENTS

Examiner Initial*	Document Number	Issue Date	Name	Class	Sub Class	Filing Date If Appropriate

FOREIGN PATENT DOCUMENTS

	Document Number	Publication Date	Country	Class	Sub Class	Translation Yes or No
W	04-123439	04/23/1992	Japan	X	X	Abstract

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)


Examiner *William M. Brunster*

Date Considered *6 AUG 05*

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